

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	738	(427/255.28).CCLS.	US-PGPUB; USPAT	OR	OFF	2007/04/23 15:06
S2	368	S1 and ((chamber or heater) with process\$3) and method	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/23 15:06
S3	152	S1 and (((chamber or heater) with process\$3) and method).clm,ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/23 15:23
S4	1973	(((chamber or heater) with process\$3) same coat\$) and method).clm,ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/23 15:24
S5	1477	(((chamber or heater) with process\$3) with coat\$) and method).clm,ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/23 15:24
S6	614	(((chamber or heater) with process\$3) with coat\$) with method).clm,ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/23 15:24
S7	28	(((chamber or heater) with process\$3) with (protective with coat\$)) with method).clm,ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/23 15:25
S8	93	"ceramic substrate heater"	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 10:38
S9	9976	("chemical vapor deposition" or (vapor near3 deposit\$3) or (CVD or \$3CVD) or ALD) and (coat\$ and ((Ru or ruthenium) and (Si or silicon)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 10:42
S10	9833	("chemical vapor deposition" or (vapor near3 deposit\$3) or (CVD or \$3CVD) or ALD) and (coat\$3 and ((Ru or ruthenium) and (Si or silicon)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 10:43
S11	468	("chemical vapor deposition" or (vapor near3 deposit\$3) or (CVD or \$3CVD) or ALD) and (coat\$3 and ((Ru or ruthenium) and (Si or silicon))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:34

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S14	50	"Ru/Si"	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 17:48
S15	3949	((Ru or ruthenium) with (Si or silicon)) with (film or \$layer or coat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 10:49
S16	670	((Ru or ruthenium) with (Si or silicon)) with (film or \$layer or coat\$3).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 10:53
S17	2560	(427/249.1,549.17,255.37,255.394, 255.7,255.28).CCLS.	US-PGPUB; USPAT	OR	OFF	2007/04/24 10:54
S18	468	S17 and (Ru or ruthenium or Re or rhenium or Ta or tantalum or Ni or nickel or Cr or chromium).clm. and (Si or silicon or oxygen or "o.sub.2" or nitrogen or "n.sub.2" or hydrocarbon).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:02
S19	16	S17 and ((ruthenium or Ru) near3 (silicon or Si))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:05
S31	6	"Ru.sub.3(CO).sub.12"	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:12
S34	14	"Ru.sub.3(CO).sub.12" or ("Ru.sub.3" adj ((Co)".sub.12" or "CO.sub.12"))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:13
S35	16	"Ru.sub.3(CO).sub.12" or ("Ru.sub.3" adj ((Co)".sub.12" or "CO.sub.12")) or Ru3CO12 or Ru3(CO)S19	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:14
S36	336	("chemical vapor deposition" or (vapor near3 deposit\$3) or (CVD or \$3CVD) or ALD) and (coat\$3 with (heater)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 11:35
S37	51	("chemical vapor deposition" or (vapor near3 deposit\$3) or (CVD or \$3CVD) or ALD) and (coat\$3 with (substrate with heater)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 12:59
S39	621	("Tri-ruthenium dodecacarbonyl") or ("ruthenium carbonyl") or ("dodecacarbonyltri-ruthenium")	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 13:03

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S40	87	S39 AND (CVD OR "CHEMICAL VAPOR DEPOSITION" OR (VAPOR NEAR DEPOSIT\$3) OR \$3CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 13:18
S41	591	S39 NOT (CARBONYL ADJ CHLORIDE)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 13:18
S42	87	S40 AND (CVD OR "CHEMICAL VAPOR DEPOSITION" OR (VAPOR NEAR DEPOSIT\$3) OR \$3CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 13:54
S44	155	(silane or monosilane) with ruthenium	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 13:56
S45	246	((silane or monosilane) with (ruthenium or ru)) or ru/si	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 13:57
S46	196	((silane or monosilane) with (ruthenium or ru))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 14:12
S49	123	ruthenium adj silicide	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 15:46
S51	13	(alternating with metal with silica layer) cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 15:47
S53	71	(alternating with metal with silicon with layer) cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 15:48
S54	21	(alternating with metal with silicon with layer).clm. cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 15:49
S59	1435	(deposit\$3 with (ruthenium or rhenium or tantalum or nickel or chromium) with (silicon or carbon or nitrogen or oxygen)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 17:43
S60	29	(deposit\$3 with (ruthenium or rhenium or tantalum or nickel or chromium) with (silicon or carbon or nitrogen or oxygen)).clm. and multilayer.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 17:47

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S61	18	(deposit\$3 with (ruthenium or rhenium or tantalum or nickel or chromium) with (silicon)).clm. and multilayer.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 17:48
S62	796	(deposit\$3 with (ruthenium or rhenium or tantalum or nickel or chromium) with (silicon)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 17:48
S63	45	(deposit\$3 with (ruthenium) with (silicon)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 17:52
S64	17	(deposit\$3 with (silicon with silane)) same (metal adj substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:01
S65	17	(((\$3CVD or deposit\$3) with (silicon with silane)) same (metal adj substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:02
S66	27	(((\$3CVD or deposit\$3) and (silicon with silane)) same (metal adj substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:02
S70	64	((silicon adj (film or coat)) same ((ru or ruthenium) adj (film or coat)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:18
S71	249	((silicon adj (film or coat)) same (metal adj (film or coat))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:19
S72	41	((silicon adj (film or coat)) same (metal adj (film or coat))).clm. and silane and (\$3cvd or deposit\$)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:25
S73	467	(metal adj layer) with ("non-metal" adj layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:26
S74	17	((metal adj layer) with ("non-metal" adj layer)) and silicon and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:27
S75	290	((metal adj layer) with (silicon adj layer)) and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:28

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S76	5	((metal adj layer) with (silicon adj layer)) and silane and ruthenium	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:38
S77	7164	sequential CVD metal silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:38
S78	36	(sequential CVD metal silicon).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:42
S80	153	"backside contamination" silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:52
S83	26	pre-coating with substrate with (holder or support or heater)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 18:57
S85	111	(protective with (\$3coating or deposit\$3) with (substrate adj (holder or support\$2 or heater)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 19:35
S89	2149	method adj process\$3 adj substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 19:37
S90	146	(method adj process\$3 adj substrate) protective coat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 19:39
S93	34	(method adj process\$3 adj substrate) (\$3CVD or "chemical vapor deposition" or (vapor adj deposit\$3) or ALD or epitaxy or etch\$3) silicon silane ruthenium	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 19:51
S94	1120	(method adj process\$3 adj substrate) (\$3CVD or "chemical vapor deposition" or (vapor adj deposit\$3) or ALD or epitaxy or etch\$3) (ru or ruthenium or metal or rhenium or re or tantalum or ta or nickel or ni or chromium or cr)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 19:53
S96	8	("0129306" "4894257" "5695832" "6610568").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/24 22:00

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S98	49	deposit\$3 non-metal layer substrate (heater or holder or support\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	SAME	ON	2007/04/30 20:28
S100	1253	((Ru or ruthenium) with (gas or vapor or precursor)) and ((Si or silicon) with (gas or vapor or precursor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 19:11
S101	266	((Ru or ruthenium) with (gas or vapor or precursor)) and ((Si or silicon) with (gas or vapor or precursor)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 19:12
S102	186	((Ru or ruthenium) with (gas or vapor or precursor)) and ((Si or silicon) with (gas or vapor or precursor)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 19:13
S103	120	((Ru or ruthenium) with (gas or vapor or precursor)) and ((Si or silicon) with (gas or vapor or precursor)) not catalyst).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 19:26
S107	8263	"barrier layer" with coating	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 19:32
S108	1005	("barrier layer" with coating).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 19:32
S109	137	("barrier layer" with coating).clm. and (CVD or (vapor adj deposit\$3)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 20:25
S110	529	method with (coat\$3 or film) with (barrier or protect\$3) with (substrate and (holder or heater or support\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 20:26
S111	117	method with (coat\$3 or film) with (barrier or protect\$3) with (substrate and (holder or heater or support\$3)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 20:27
S112	13	method with (coat\$3 or film) with (barrier or protect\$3) with (substrate adj (holder or heater or support\$3)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 20:31
S113	56	method with (coat\$3 or film) with (barrier or protect\$3) with (substrate adj (holder or heater or support\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/25 21:11

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S14 5	83	CVD WITH APPARATUS WITH "BARRIER LAYER"	US-PGPUB; USPAT; EPO; JPO; DERWENT	SAME	ON	2007/04/30 20:38
S14 7	109	"DIFFUSION BARRIER LAYER" WITH CONTAMINATION	US-PGPUB; USPAT; EPO; JPO; DERWENT	SAME	ON	2007/04/30 20:59
S15 2	11	"backside contamination" with ceramic	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/30 21:11
S15 3	96	("backside contamination" or (substrate near3 contamination)) with ceramic	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/30 21:14